

(19)

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(11)

EP 1 045 291 A3

(12)

EUROPEAN PATENT APPLICATION

(88) Date of publication A3:
10.01.2001 Bulletin 2001/02

(51) Int. Cl? G03F 7/40

(43) Date of publication A2:
18.10.2000 Bulletin 2000/42

(21) Application number: 00101348.1

(22) Date of filing: 24.01.2000

(84) Designated Contracting States:
AT BE CH CY DE DK ES FI FR GB GR IE IT LU
MC NL PT SE
Designated Extension States:
AL LT LV MK RO SI

(30) Priority: 17.02.1999 US 250861

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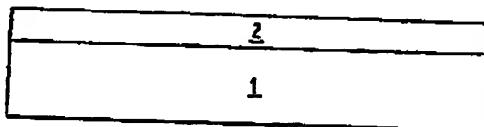
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(54) Method of Improving the etch resistance of photoresists

(57) A photoresist system is provided that is easily structurable and is suitable for deep ultraviolet range patterning. An increased etching resistance to halogen-containing plasma is produced in a lithographically generated photoresist structure by treatment with an etch protectant. The etch protectant comprises predominantly aromatic structures and includes reactive groups that are suitable for chemical reaction with reactive

groups of the photoresist. In an embodiment, the photoresist includes a base resin containing no aromatic groups prior to reaction with the aromatic etch protectant. The etch protectant preferably includes an aromatic polycarboxylic acid, aromatic polycarboxylic acid anhydride, or aromatic polycarboxylic acid chloride.

FIG. 1



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EUROPEAN SEARCH REPORT

Application Number
EP 00 10 1348

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Place of search		Date of completion of the search	Examiner
MUNICH		17 November 2000	Thiele, N
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X : particularly relevant to claim Y : particularly relevant if combined with another document of the same category A : technological background C : non-technical disclosure P : Priorities document			
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